Application No.	Applicant(s)
10/812 880	EGASHIRA ET AL.
Examiner	Art Unit
David Nhu	2818
pears on the cover sheet wite S (OR REMAINS) CLOSED in S) or other appropriate commu	h the correspondence address this application. If not included nication will be mailed in due course. THIS ubject to withdrawal from issue at the initiative
" of this communication to file MENT of this application. mitted. Note the attached EXA ves reason(s) why the oath or ust be submitted. rson's Patent Drawing Review	in No I in this national stage application from the a reply complying with the requirements MINER'S AMENDMENT or NOTICE OF declaration is deficient. (PTO-948) attached in the Office action of e drawings in the front (not the back) of R 1.121(d). RIAL must be submitted. Note the
6. ☐ Interview Su Paper No./N 7. ☐ Examiner's A 8. ☑ Examiner's S 9. ☐ Other	ormal Patent Application mmary (PTO-413), Mail Date Amendment/Comment Statement of Reasons for Allowance
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REASONS FOR ALLOWANCE

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1. Claims 12-19 are allowed.

2. The following is an examiner's statement of reasons for allowance: None of the references of record teaches or suggests as cited in claims 12: an interconnect made of a first conductive film and a second conductive film that are stacked in sequence from the interconnect underside on the insulating film; an upper capacitor electrode made of the second conductive film and formed on the dielectric film, where each of the lower capacitor electrode, the dielectric film, and the upper capacitor electrode has a same pattern; and lower contacts are formed in the insulating film on a bottom surface of the lower capacitor electrode, the lower contacts being connected to the lower capacitor electrode.

3. Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

CONCLUSION

4. The prior art made of record and not relied upon is considered pertinent to applicant's disclosure: Lachner (6,893,935 B2): Semiconductor Component and Fabrication Method.

5. Any inquiry concerning this communication on earlier communications from the examiner should be directed to David Nhu, (571)272-1792. The examiner can normally be reached on Monday-Friday from 7:30 AM to 5:00 PM.

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The fax phone number for the organization where this application or proceeding is assigned is (571)273-8300.

David Nhu

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November 22, 2006

DAVID NHU PRIMARY EVALUATION